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APPLICATION NO.		FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/695,969		10/29/2003	Hiroaki Ohkubo	NECF 20.702	7995	
26304	7590	06/09/2004		EXAMINER		
		IIN ZAVIS ROSI	FARAHANI, DANA			
	DISON AVENUE DRK, NY 10022-2585			ART UNIT	PAPER NUMBER	
	,			2814		
				DATE MAILED: 06/09/2004		

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)					
Office Action Commence	10/695,969	OHKUBO ET AL.					
Office Action Summary	Examiner	Art Unit					
	Dana Farahani	2814					
The MAILING DATE of this communication app Period for Reply	ears on the cover sheet with the c	correspondence address					
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION. - Extensions of time may be available under the provisions of 37 CFR 1.13 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a reply If NO period for reply is specified above, the maximum statutory period w - Failure to reply within the set or extended period for reply will, by statute, Any reply received by the Office later than three months after the mailing earned patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however, may a reply be tir within the statutory minimum of thirty (30) day will apply and will expire SIX (6) MONTHS from cause the application to become ABANDONE	nely filed vs will be considered timely. In the mailing date of this communication. ED (35 U.S.C. § 133).					
Status							
1) Responsive to communication(s) filed on <u>29 October 2003</u> .							
2a) ☐ This action is FINAL . 2b) ☒ This	This action is FINAL . 2b)⊠ This action is non-final.						
·— ··	Since this application is in condition for allowance except for formal matters, prosecution as to the merits is closed in accordance with the practice under <i>Ex parte Quayle</i> , 1935 C.D. 11, 453 O.G. 213.						
Disposition of Claims							
 4) ☐ Claim(s) 1-9 is/are pending in the application. 4a) Of the above claim(s) is/are withdray 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 1-9 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and/or 							
Application Papers							
9) The specification is objected to by the Examiner.							
I0)☐ The drawing(s) filed on is/are: a)☐ accepted or b)☐ objected to by the Examiner.							
Applicant may not request that any objection to the drawing(s) be held in abeyance. See 37 CFR 1.85(a).							
Replacement drawing sheet(s) including the correct 11) The oath or declaration is objected to by the Ex	· · · · · · · · · · · · · · · · · · ·						
Priority under 35 U.S.C. § 119							
12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documents 2. Certified copies of the priority documents 3. Copies of the certified copies of the priority application from the International Bureau * See the attached detailed Office action for a list	s have been received. s have been received in Applicat rity documents have been receive u (PCT Rule 17.2(a)).	ion No ed in this National Stage					
Attachment(s)	_						
Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948)	4)						
 2) Notice of Draftsperson's Patent Drawing Review (PTO-948) 3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08) Paper No(s)/Mail Date 	_ ' ' ' '	Patent Application (PTO-152)					

DETAILED ACTION

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.
- 2. Claims 1, 4, 6, and 9 are rejected under 35 U.S.C. 102(b) as being anticipated by the Japanese patent 02037746 A, issued to Nobuhara.

The Japanese patent discloses in figure 1, a semiconductor integrated circuit, comprising a support substrate 2; a semiconductor layer 6 that is formed on the entire surface of the support substrate and has a lower resistivity than the resistivity of the support substrate; and first and second circuit sections 12 formed in the semiconductor layer in an electrically isolated state from each other.

Claim Rejections - 35 USC § 103

- 3. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which the subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 4. Claim 2, 3, 7, and 8 are rejected under 35 U.S.C. 103(a) as being unpatentable over the Japanese patent.

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The Japanese patent substantially discloses the claimed invention, as discussed above, except for expressly disclosing the resistivity of the support substrate is 20 or 50 times or more the resistivity of the semiconductor layer. It would have been obvious to one of ordinary skill in the art at the time the invention was made to select the relative resistivity of the substrate and the semiconductor layer, since it has been held that discovering an optimum value of a result effective variable involves routine skill in the art. *In re Boesch*, 617 F.2d 272, 205 USPQ 215 (CCPA 1980).

5. Claims 5 and 10 are rejected under 35 U.S.C. 103(a) as being unpatentable over the Japanese patent as applied to claim 1 above, and further in view of the Applicant's Admitted Prior Art (AAPA).

The Japanese patent substantially discloses the claimed invention, as discussed above, except for expressly disclosing in the abstract that an analog circuit and a digital circuit is formed on the first and second circuit sections.

AAPA discloses in figure 1 of the instant application that on a substrate 101 a digital circuit 102 and an analog circuit 103 is formed. Therefore, it would have been obvious to one of ordinary skill in the art at the time the invention was made to make an analog and a digital circuit on the same substrate in the Japanese patent, since it is well known in the art that in some circuit applications both an analog and a digital circuit must be present on the same substrate in order for the circuitry to be usable in that application.

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Product-by-Process Limitations

A comparison of the recited process with the prior art process does NOT serve to resolve the issue concerning patentability of the product. *In re Fessman*, 489 F2d 742, 180 USPQ 324 (CCPA 1974). Whether a product is patentable depends on whether it is known in the art or it is obvious, and is not governed by whether the process by which is made is patentable. *In re Klug*, 333 F2d 905, 142 USPQ 161 (CCPA 1964). In an ex parte case, product by process claims are not constructed as being limited to the product formed by the specific process recited. In re Hirao et al., 535 F2d 67, 190 USPQ 15, see footnote 3 (CCPA 1976). Therefore, in claims 4 and 9, the semiconductor layer being formed by epitaxial growth is given no patentable weight.

Conclusion

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Dana Farahani whose telephone number is (571)272-1706. The examiner can normally be reached on M-F 9:00AM - 6:00PM.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Wael M Fahmy can be reached on (571)272-1705. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

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Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

D. Farahani

LONG PHAM PRIMARY EXAMINER